



Figure 1: Cross Sectional View of Semiconductor Device

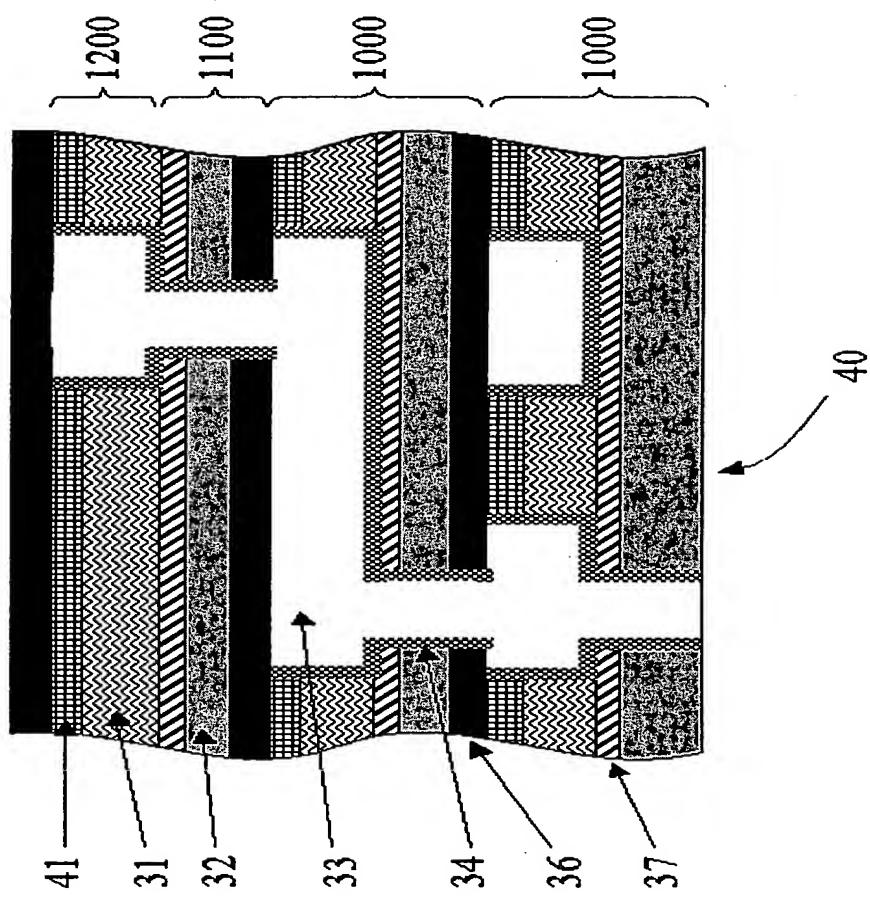


Figure 2: Cross Sectional View of Semiconductor Device

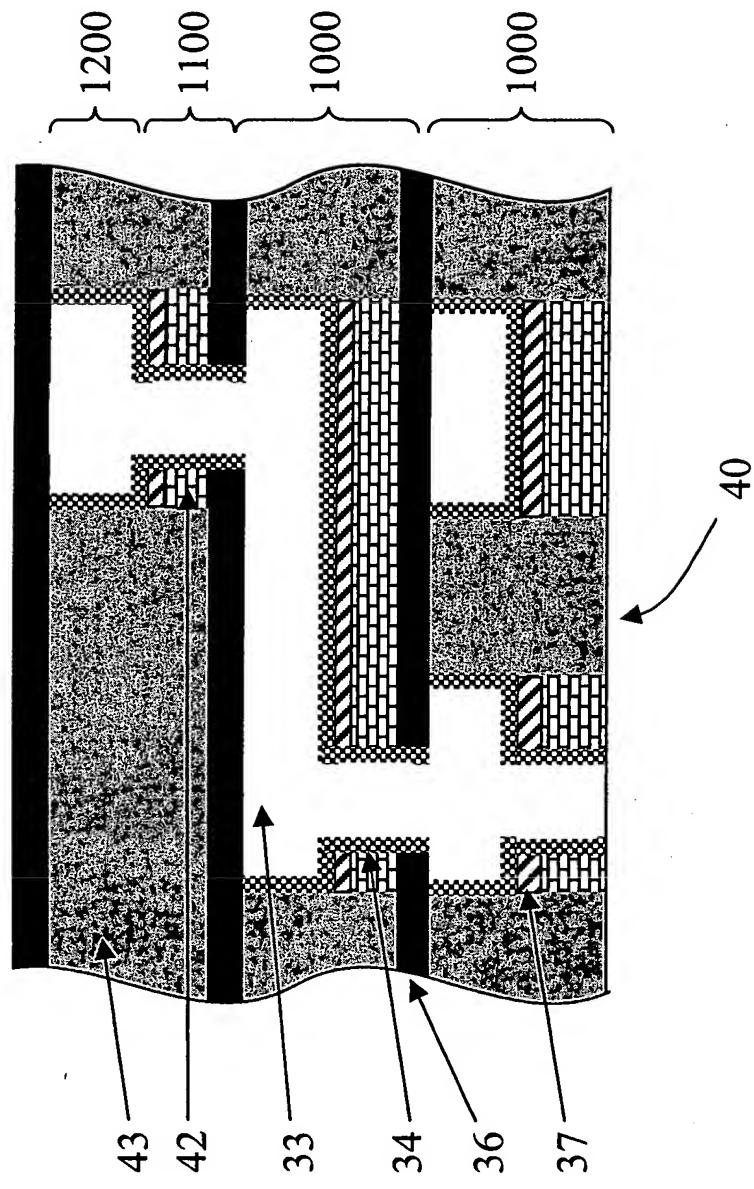


Figure 3: General Process Flow for Generation of Ceramic Diffusion Barrier Layer

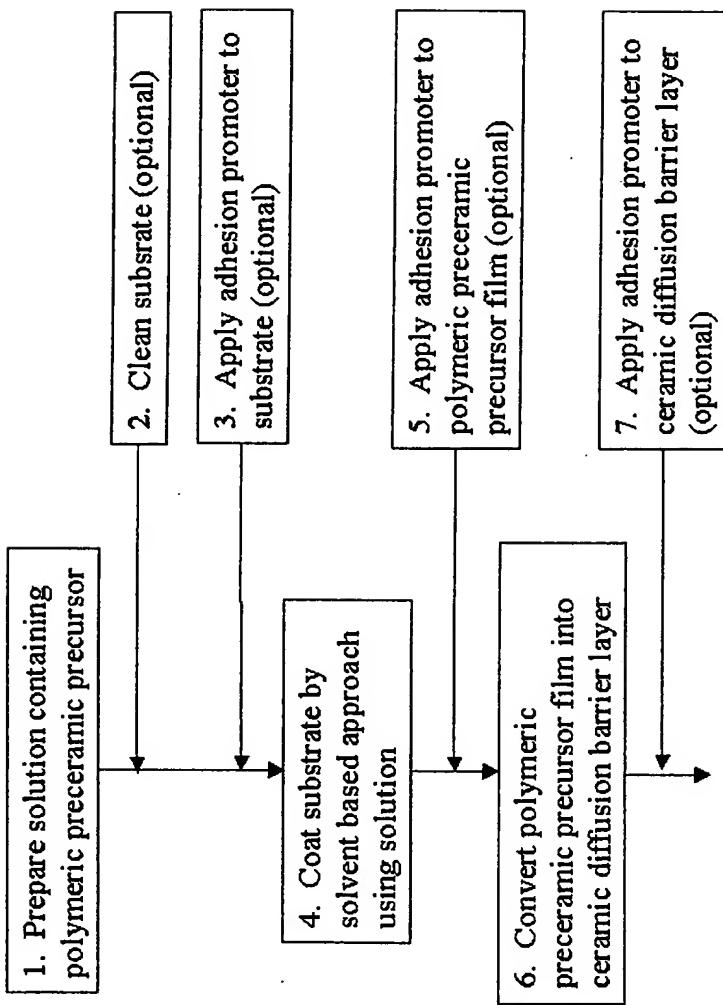


Figure 4: Electrical Data of Ceramic Diffusion Barrier Layer Generated from Polysilazane Polymer Preceramic Precursor

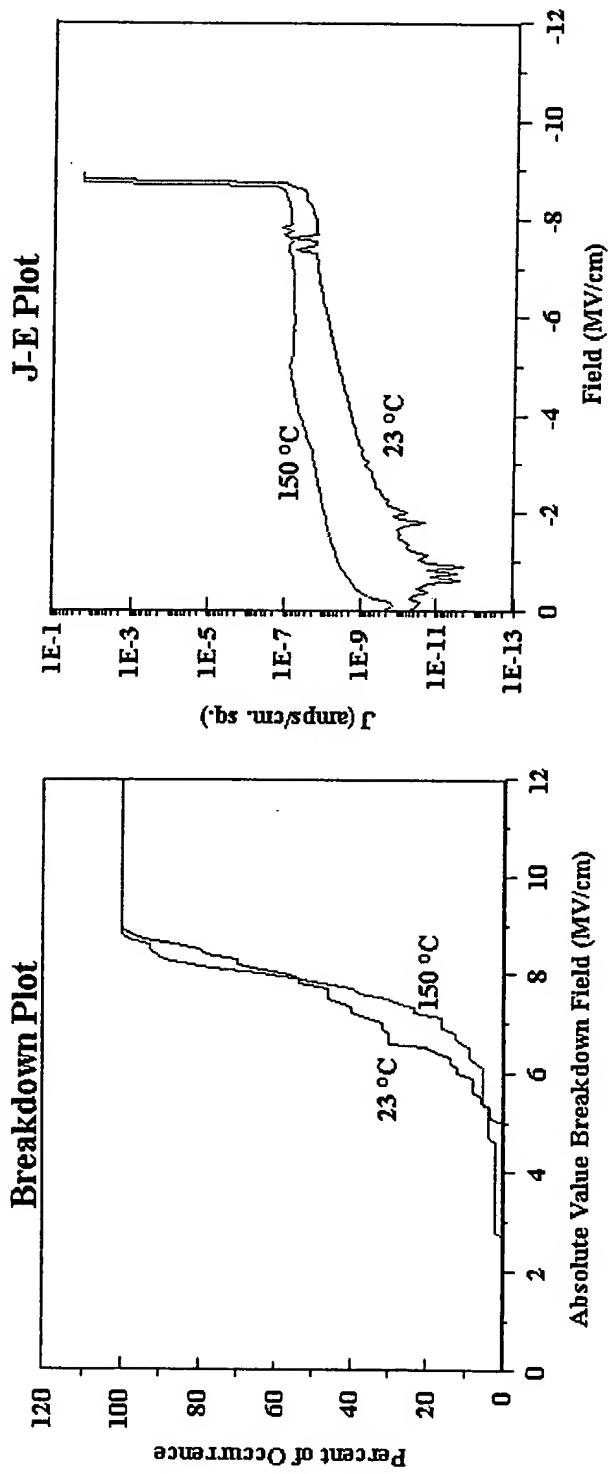


Fig. 4A

Fig. 4B